## **EAST Search History**

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L3		("hard mask" and (nitride or SiN or "silicon nitride") and (ARC or antireflect) and (resist or photoresist) and "etch stop" and plug and contact). clm.	US-PGPUB	OR	OFF	2006/03/23 09:48
L4	2	("hard mask" and (nitride or SiN or "silicon nitride") and (ARC or antireflect) and (resist or photoresist) and "etch stop" and plug and contact). clm.	US-PGPUB	OR 	ON	2006/03/23 09:51
L5	30	lee-min-suk.in.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/23 09:52
L6	82	lee-sung-kwon.in.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/23 09:53